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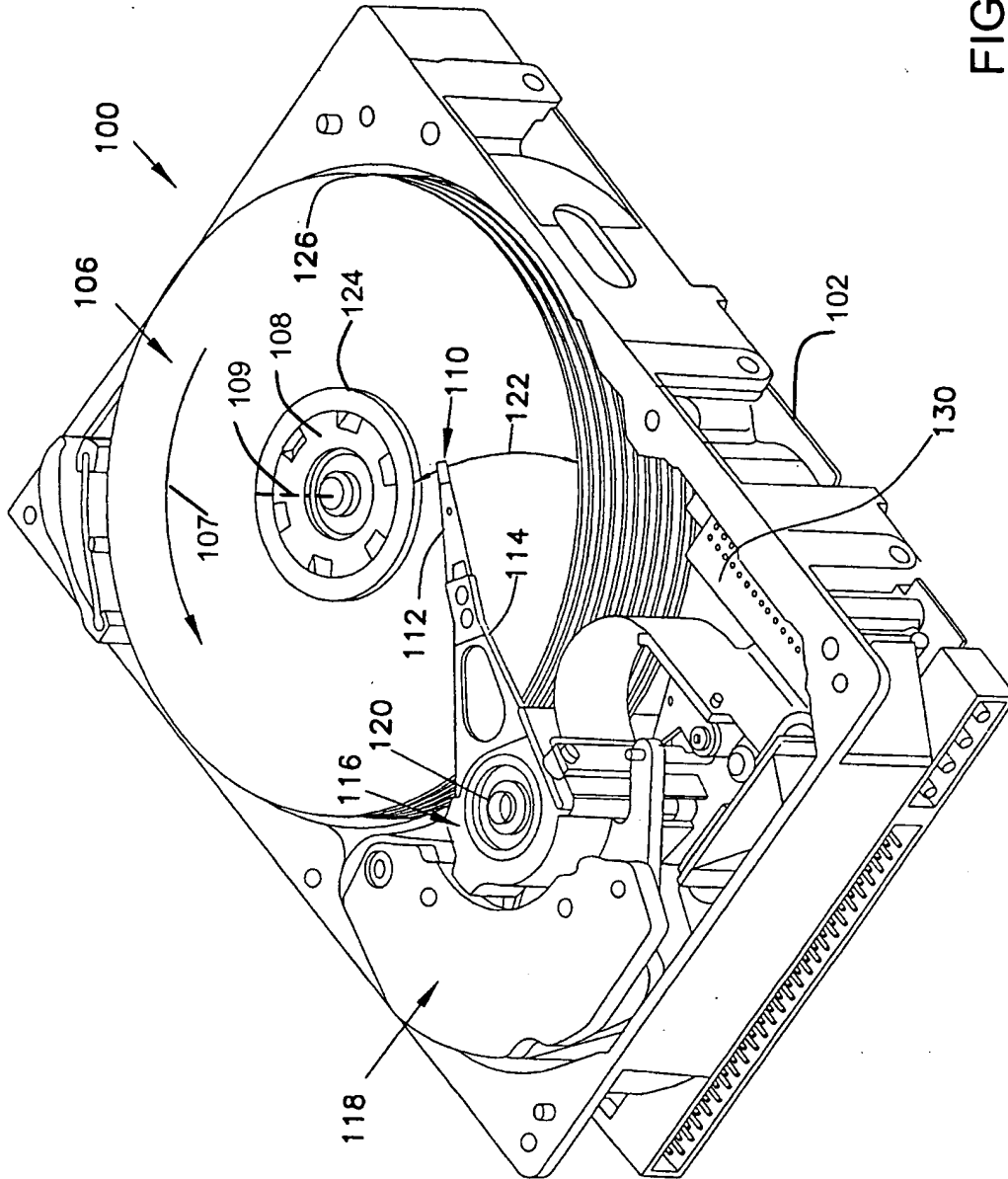


FIG. 1

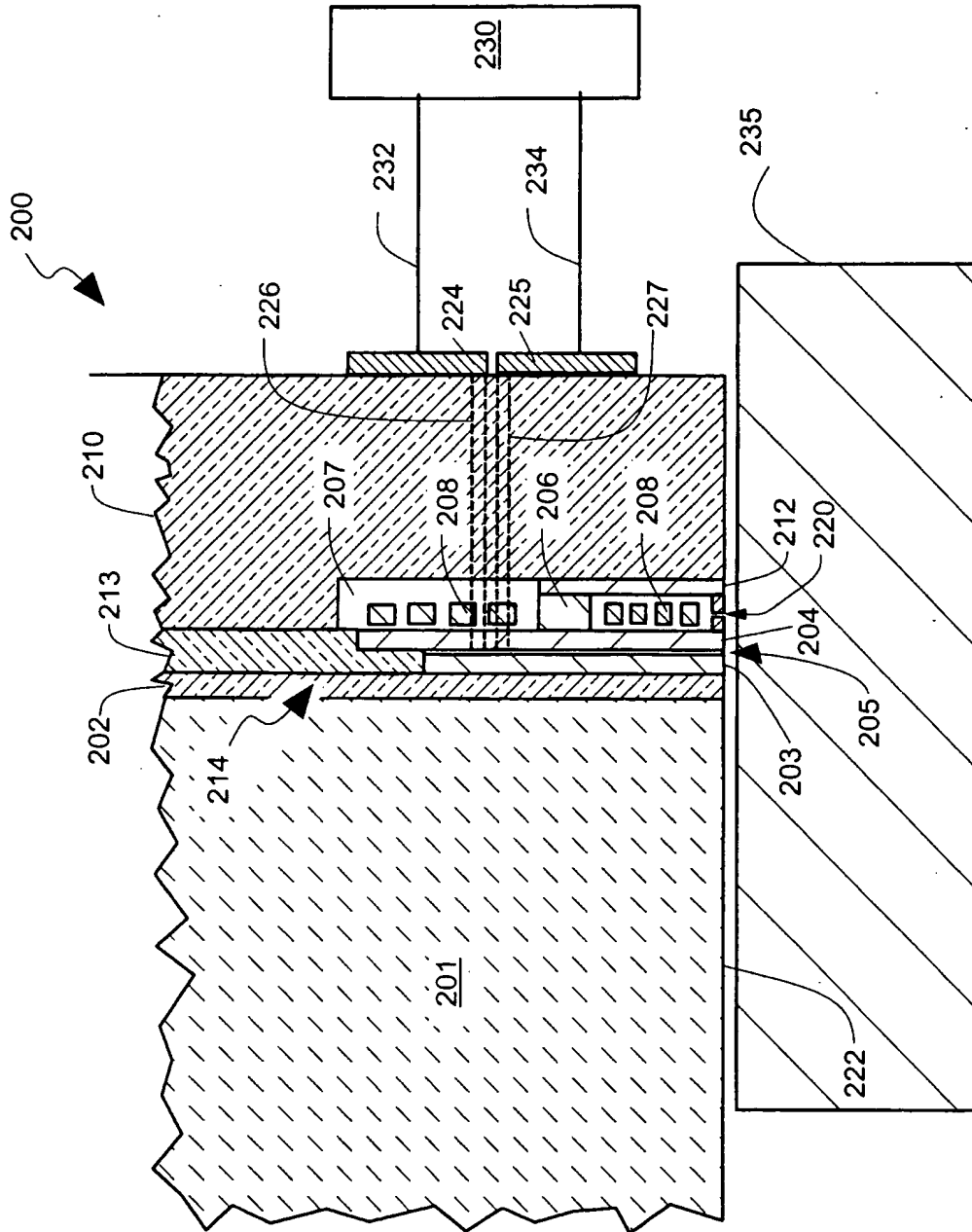


FIG. 2

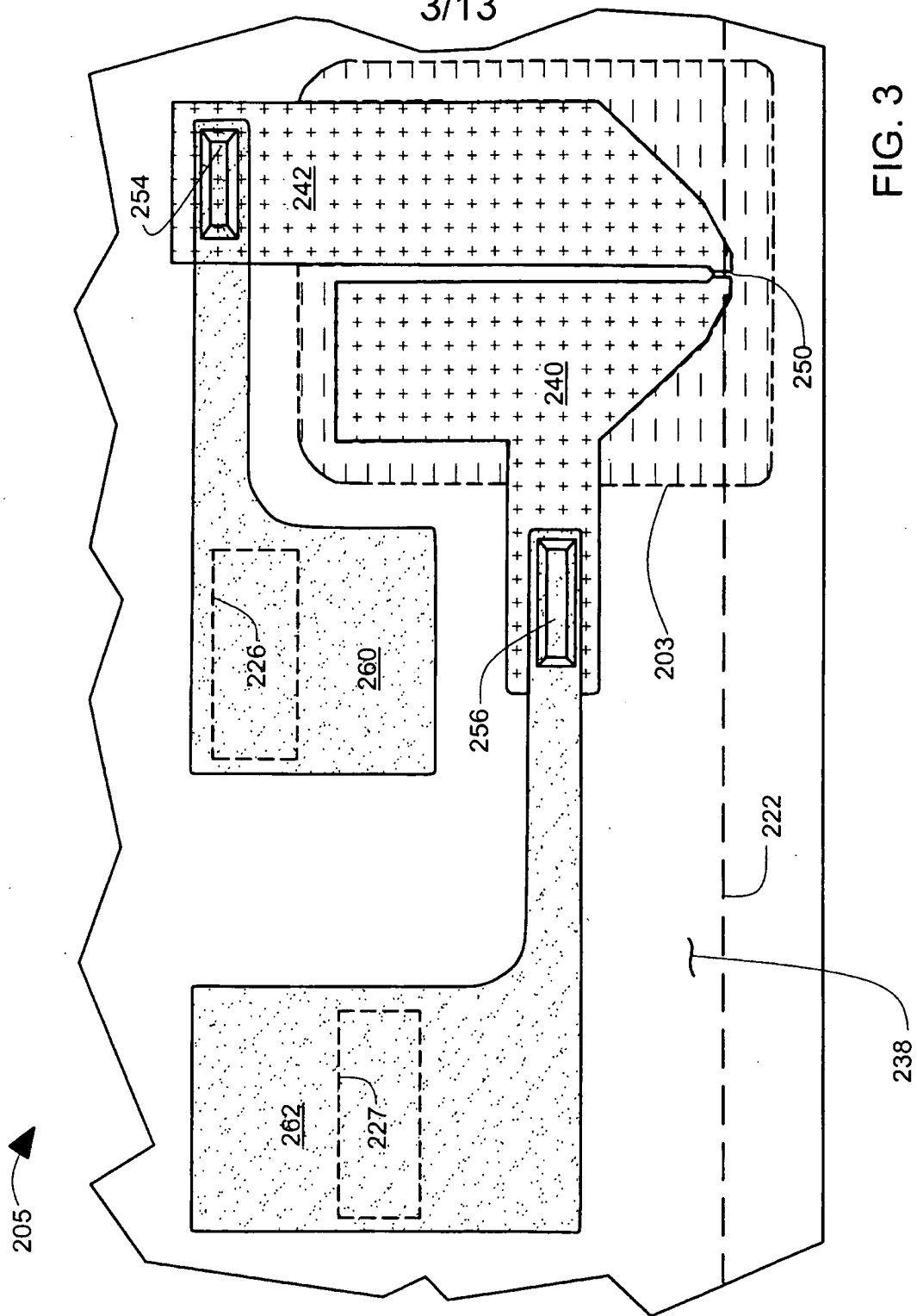


FIG. 3

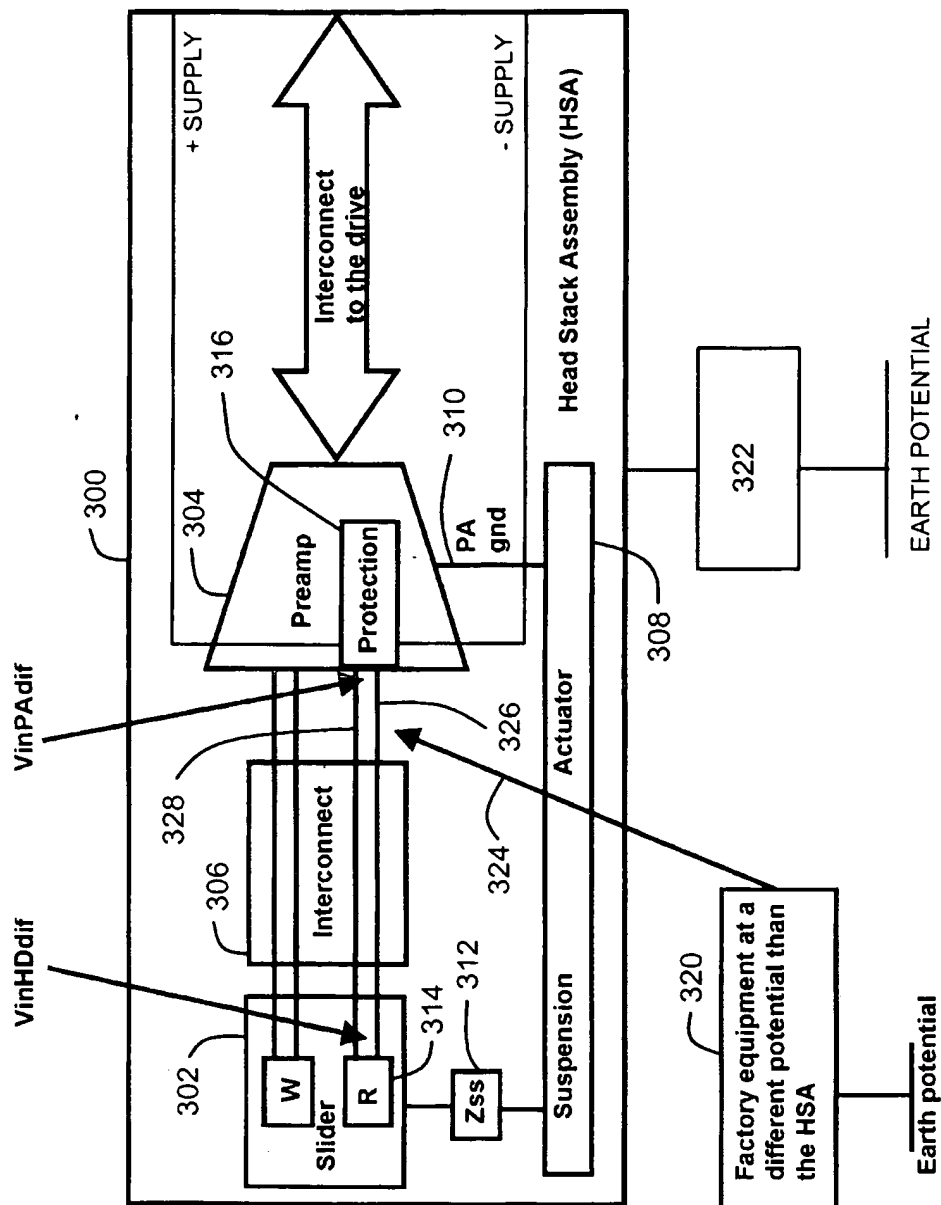
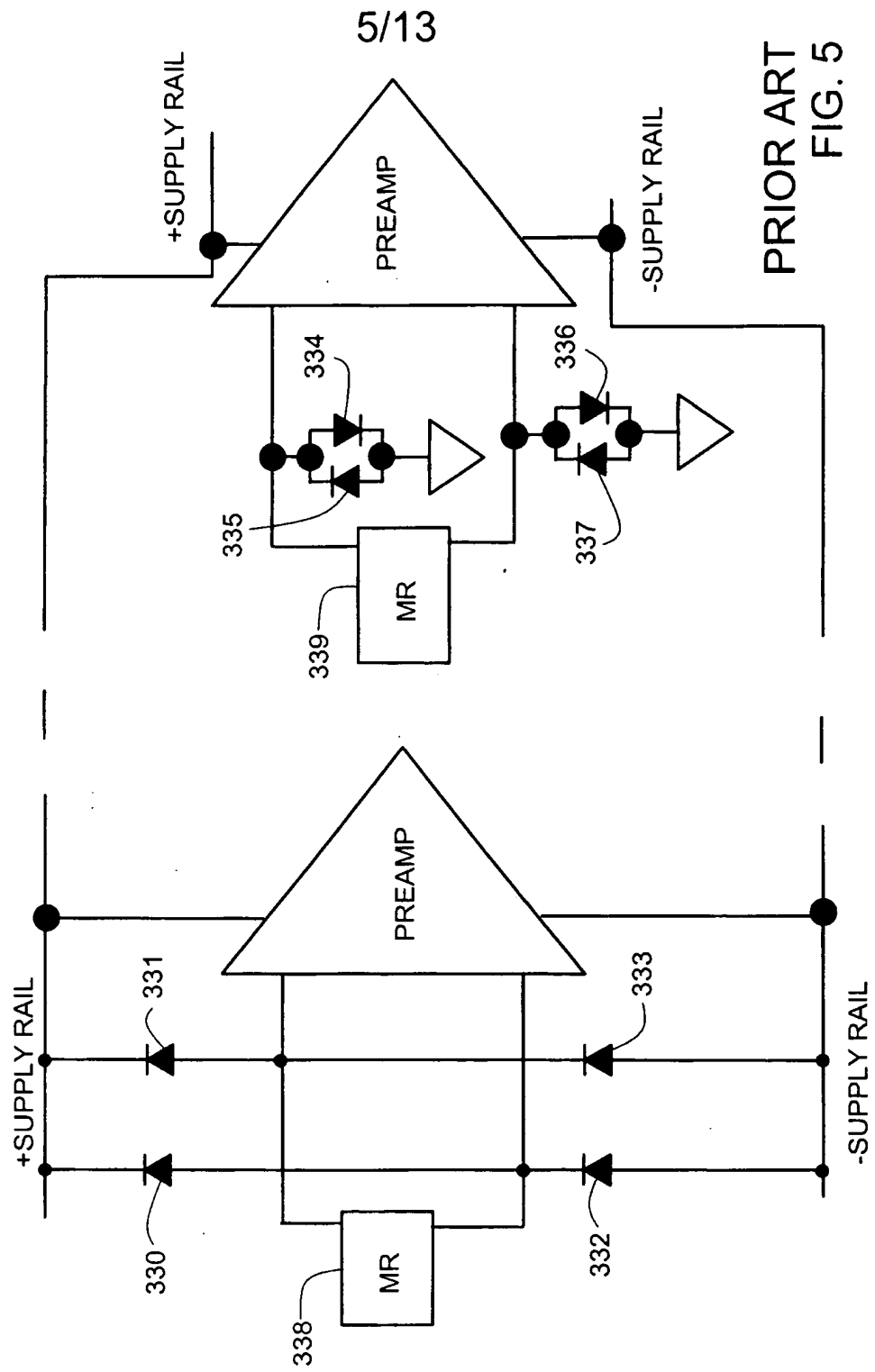


FIG. 4



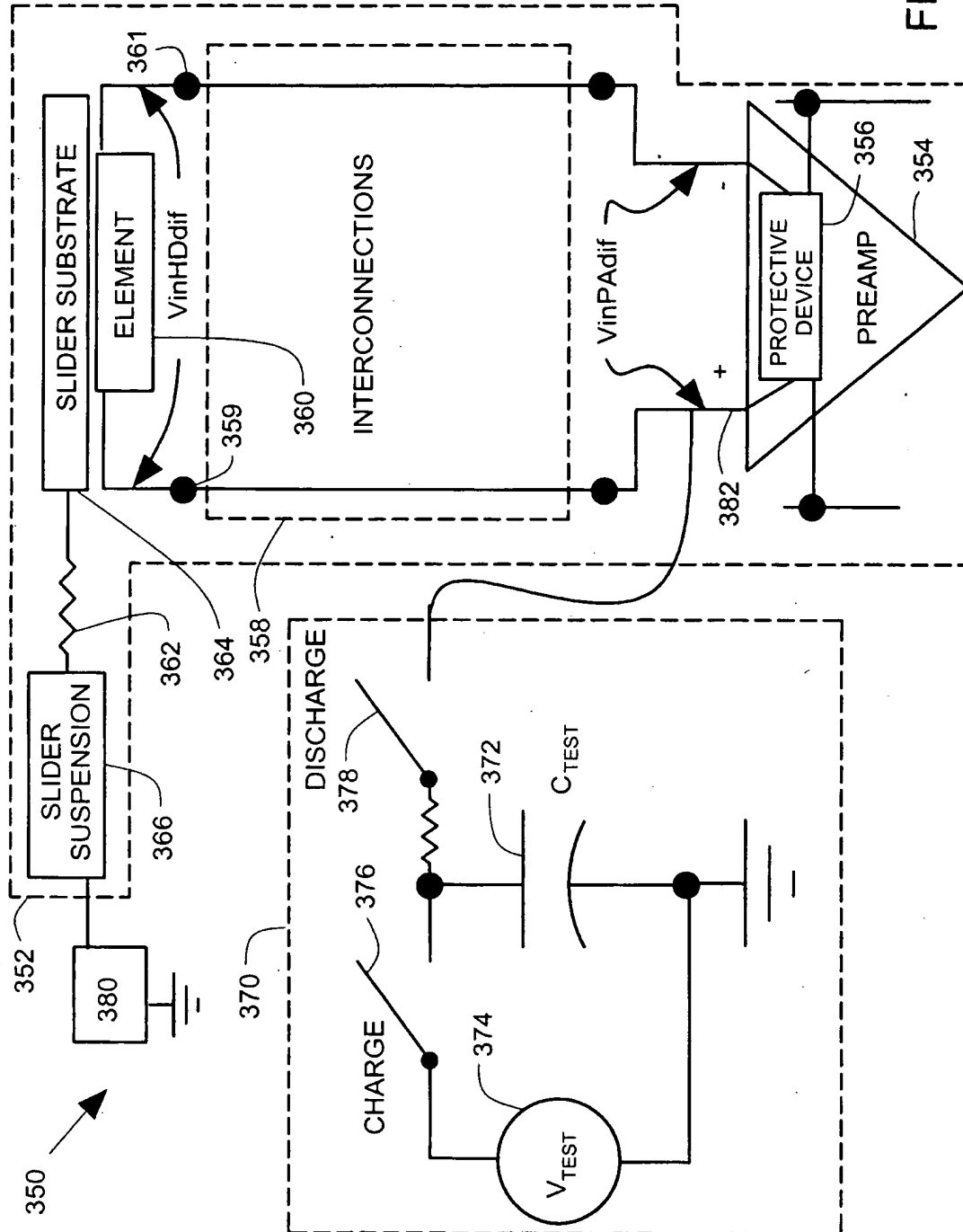


FIG. 6

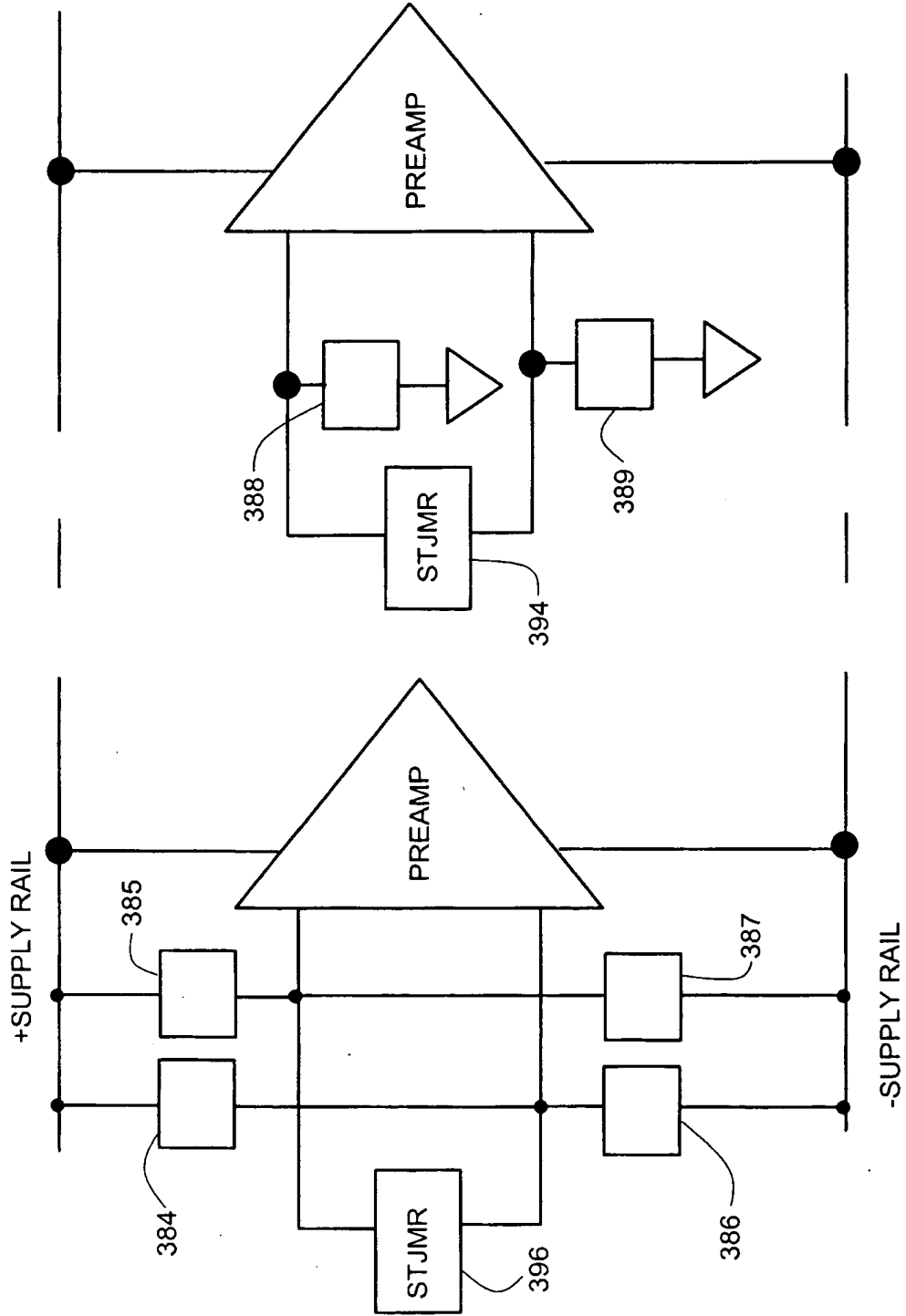


FIG. 7



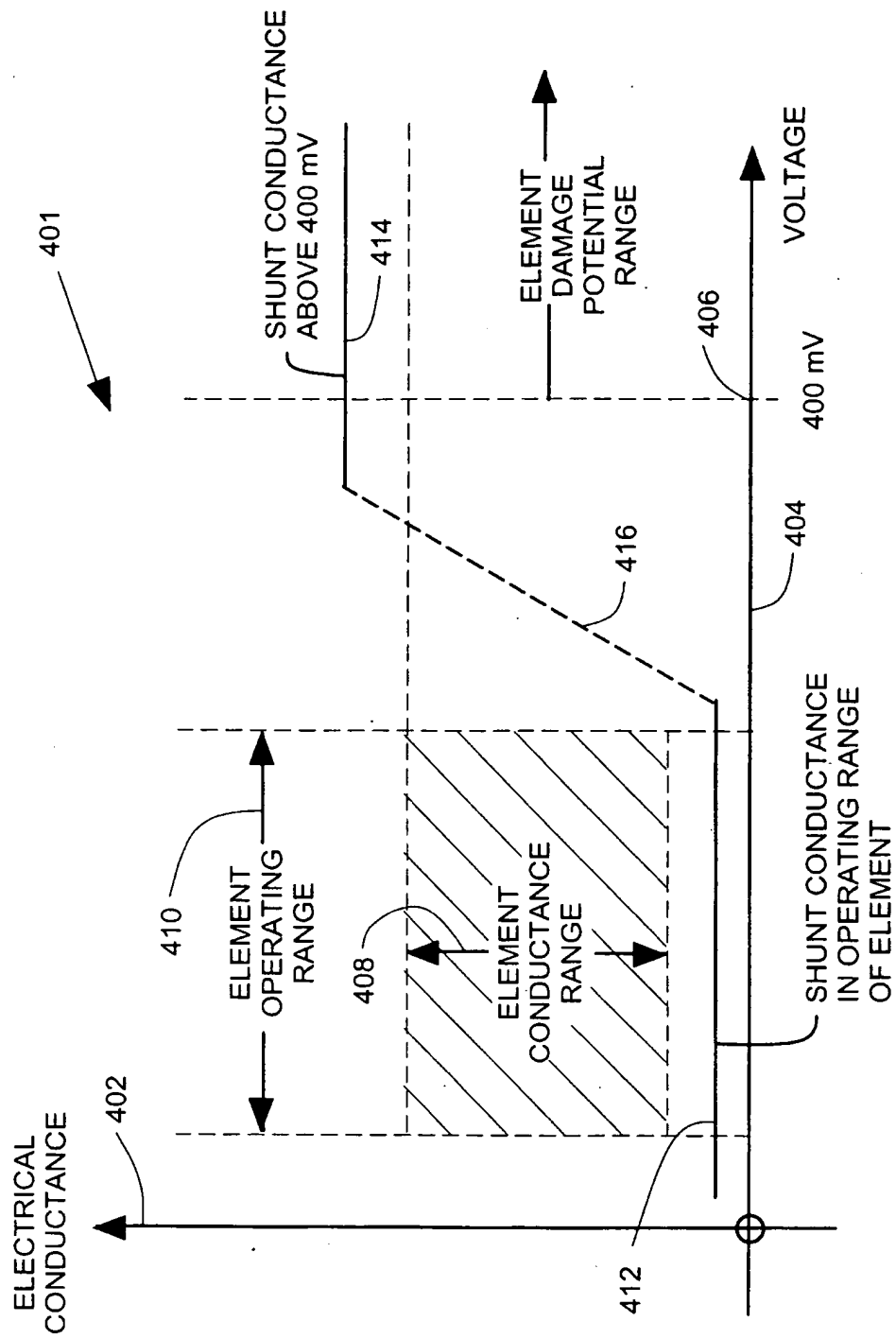


FIG. 8

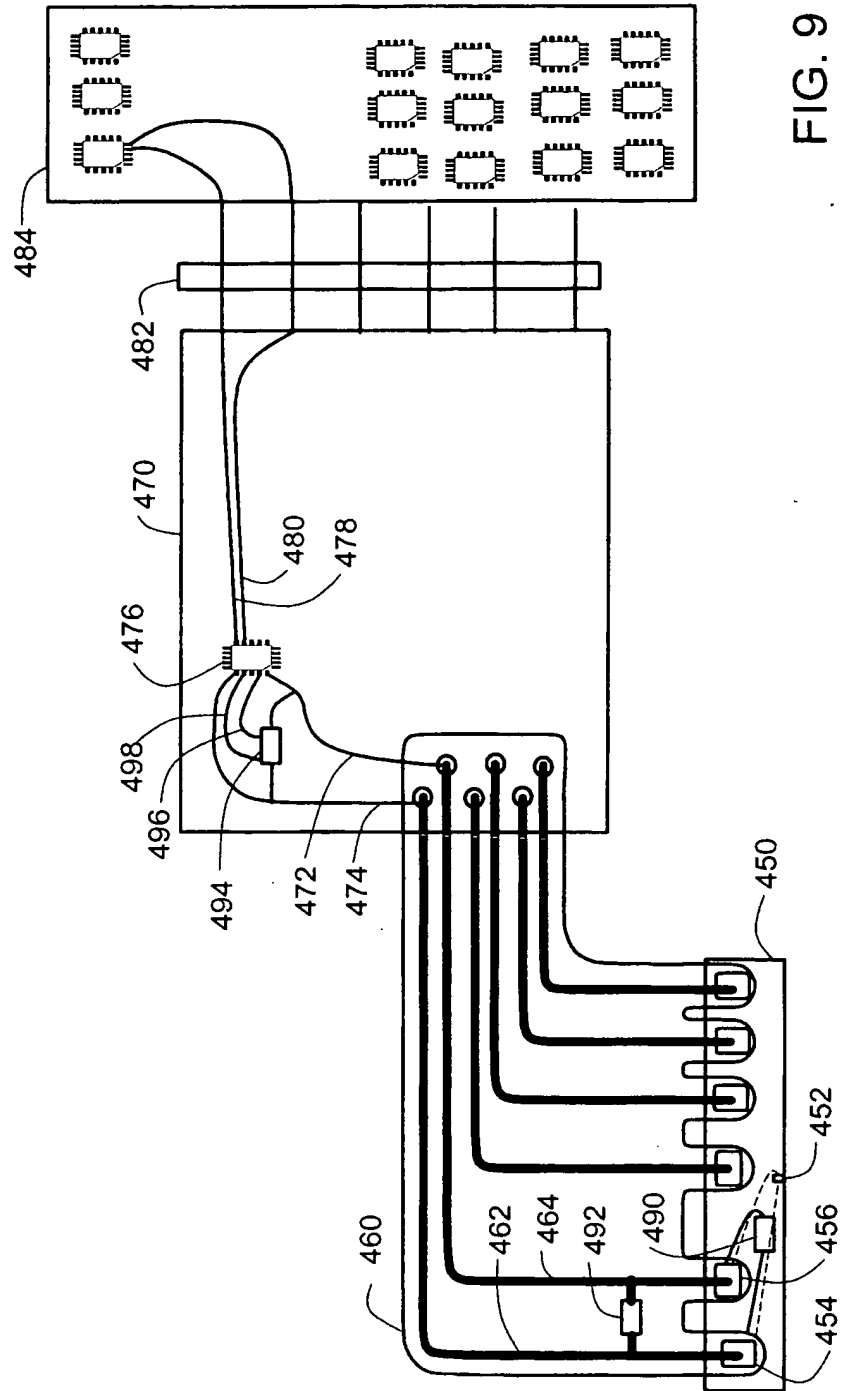
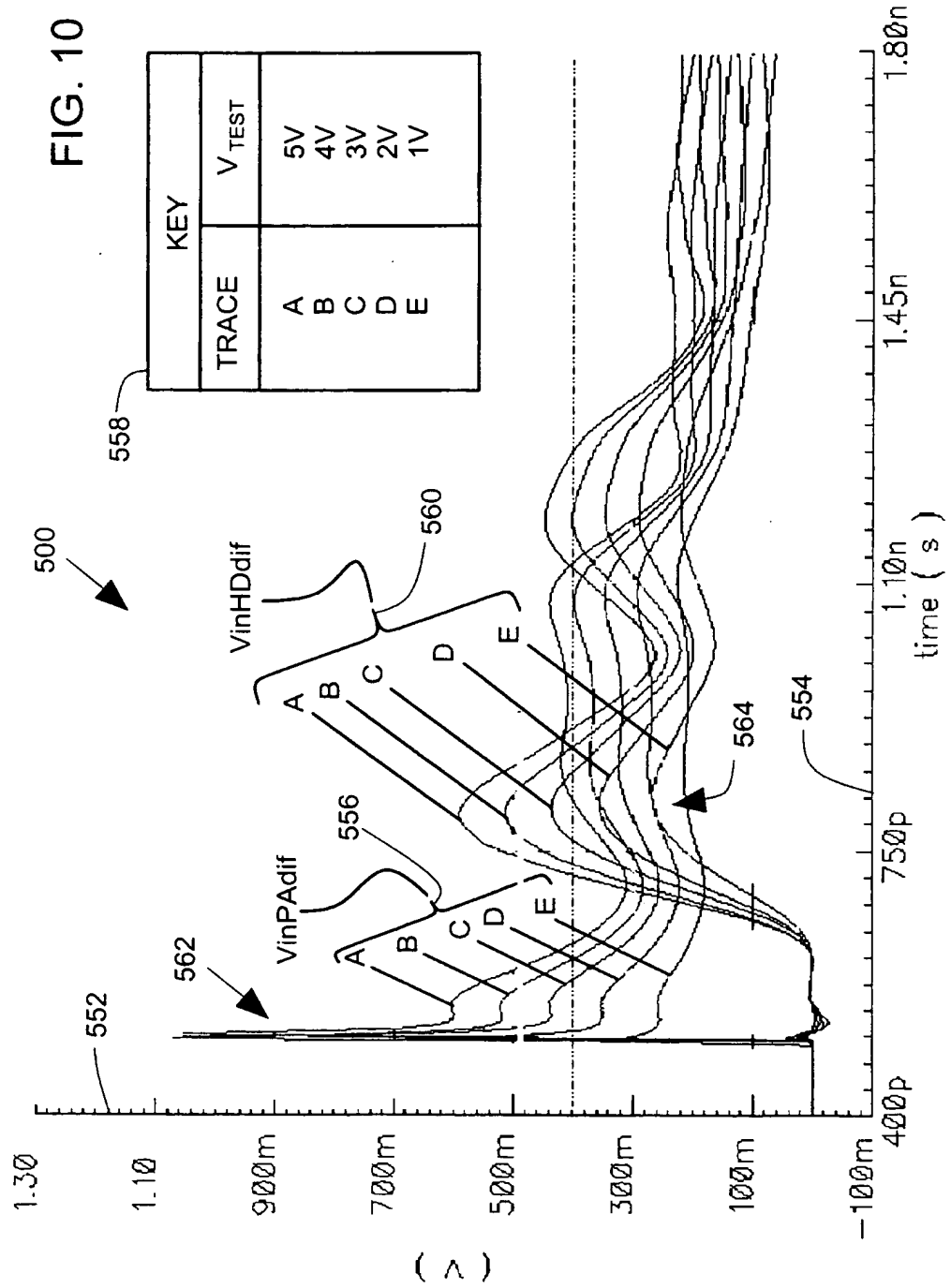


FIG. 9



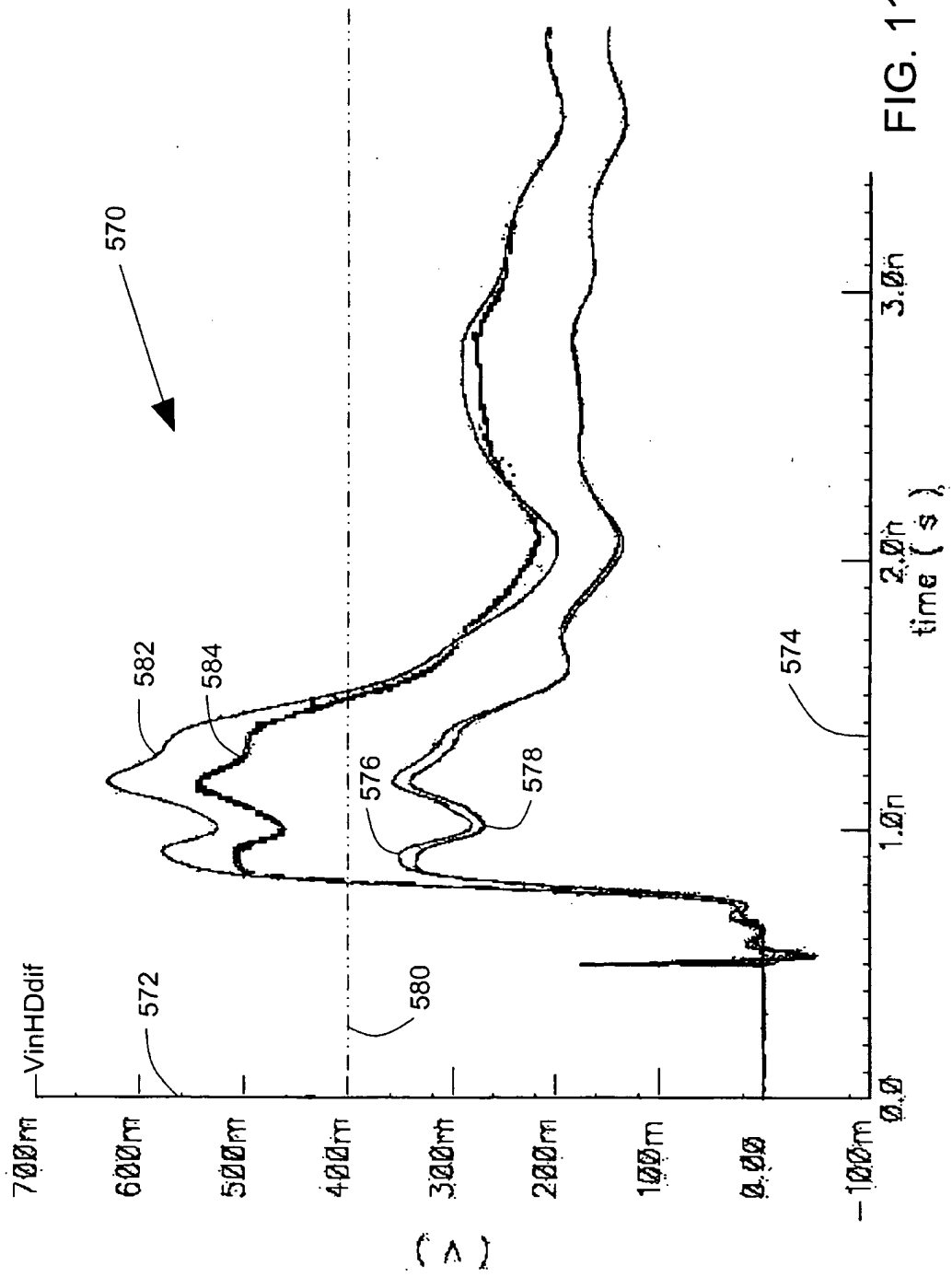


FIG. 11

Schottky metal    *Anode*

590

*Schottky*

N-epi  
N+ substrate    *Cathode*

Schottky metal/  
Ohmic contact    *Anode*

594

*JBS*

N-epi  
N- substrate    *Cathode*

Junction Schottky Barrier

Schottky contact    *Anode*

596

TMBS

SiO<sub>2</sub>

N- epi  
N+ substrate    *Cathode*

Trench MOS Schottky Barrier

FIG. 12

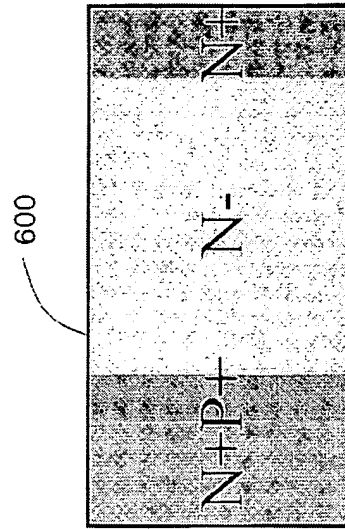


FIG. 13